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	Application No.	Applicant(s)	,
	10/032,542	ENDO ET AL.	_
Notice of Allowability	Examiner	Art Unit	
	Daborah Chacko-Davis	1756	
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in th or other appropriate communic IGHTS. This application is subj	is application. If not include ation will be mailed in due	ed course. THIS
1. X This communication is responsive to 12/16/2003.			
2. The allowed claim(s) is/are <u>1-9</u> .			
3. \boxtimes The drawings filed on <u>01/02/2002</u> are accepted by the Exa	miner.		
4. Acknowledgment is made of a claim for foreign priority ur a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submained in the su	e been received. e been received in Application Notuments have been received in of this communication to file a received in the second of this application. itted. Note the attached EXAMI are reason(s) why the oath or desire the submitted. Son's Patent Drawing Review (Inc.) as Amendment / Comment or in the second of the se	this national stage applicated the complying with the reconstruction is deficient. PTO-948) attached the Office action of the complying in the front (not the complying in the submitted. If the submitted. If the complying in the submitted is the complying in the submitted. If the complying in the submitted is the complying in the submitted in the complying in the submitted in the complying in the submitted is the complying in the submitted in the complying in the submitted is the complying in the submitted in the complying in the complying in the submitted in the complying in the compl	quirements IOTICE OF
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Sum Paper No./Ma 98), 7. ☑ Examiner's Am	il Date	

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47.50

EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Ramyar M. Farid on March 15, 2004.

The application has been amended as follows: Claim 8, line 2, after the word "aromatic" the word –compound-- has been inserted.

The preceding amendment was made to make the claim clear.

2. The following is an examiner's statement of reasons for allowance: Claims 1-5, are allowable over the prior art of record (U. S. Patent No. 6,280,898 (Hasegawa et al)) because the prior art of record fails to disclose a pattern formation method comprising forming a chemical amplified resist film wherein the resist includes a base polymer having a lactone group and having neither a hydroxyl group nor a carboxylic group, and an acid generator, and irradiating the resist film with a wavelength of a 1nm through 30nm band for pattern exposure. Claims 6-9, are allowable over the prior art of record (U. S. Patent No. 6,280,898 (Hasewaga et al)) because the prior art of record fails to disclose a pattern formation method comprising forming a chemically amplified resist film, the resist film including a base polymer, an acid generator, and an aromatic

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compound that does not generate acid during exposure, and irradiating the resist film with a wavelength of a 1nm through a 30nm band through a mask for exposure.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic

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Business Center (EBC) at 866-217-9197 (toll-free).

dcd

March 16, 2004.

MARK F. HUFF SUPERVISORY PATENT EXAMINED TECHNOLOGY TENTER TO YES

> MARK F. HUFF SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 1700